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Supplementary materials

Improving Photoelectrochemical Activity of Magnetron-Sputtered Double-Layer Tungsten Trioxide Photoanodes by Irradiation with Intense Pulsed Ion Beams

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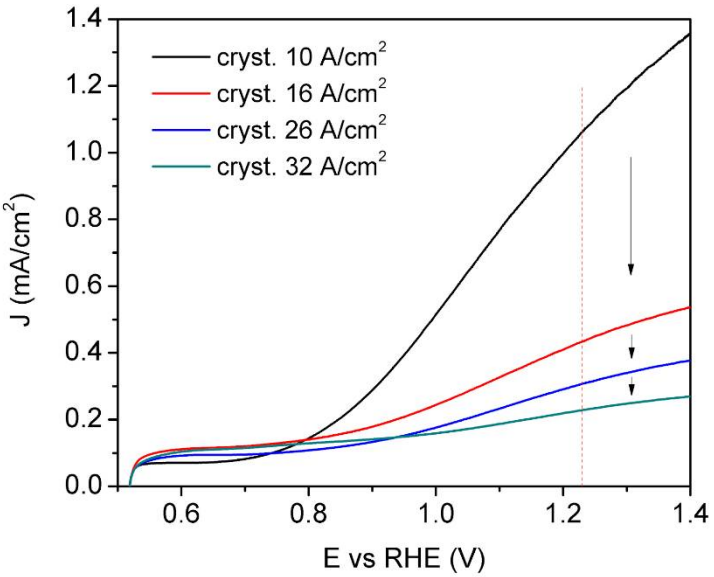

Figure S1. LSV curves of irradiated crystalline WO_3 thin films with increasing ion beam current density. Black arrows indicate that photocurrent generation reduces with increasing ion beam current densities.

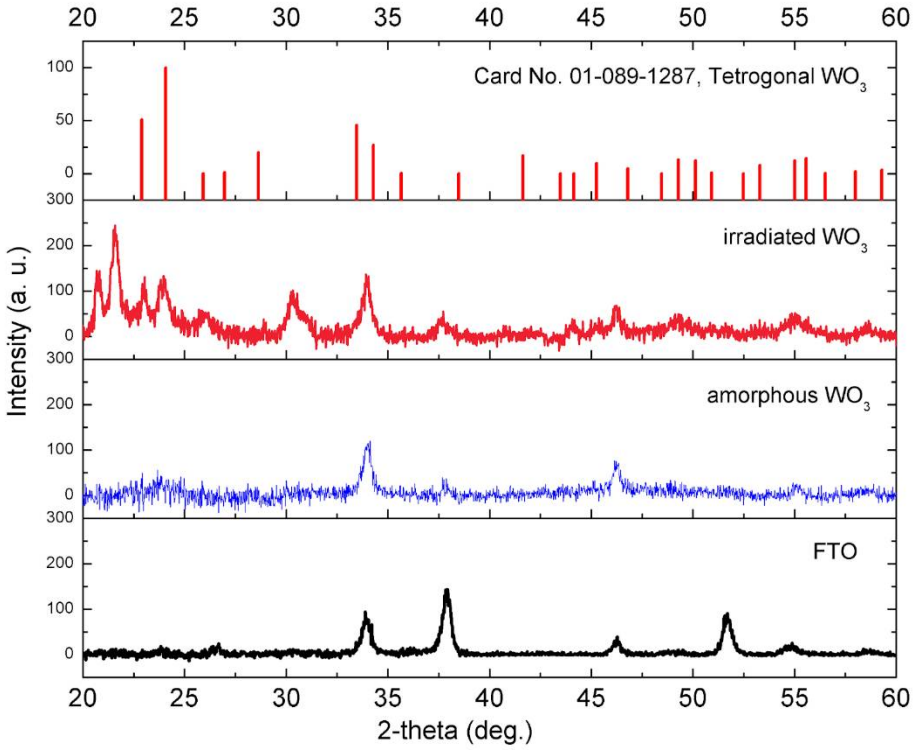

Figure S2. GI-XRD patterns of initially amorphous WO_3 thin film before and after irradiation with 6 A/cm² ion beam current density.

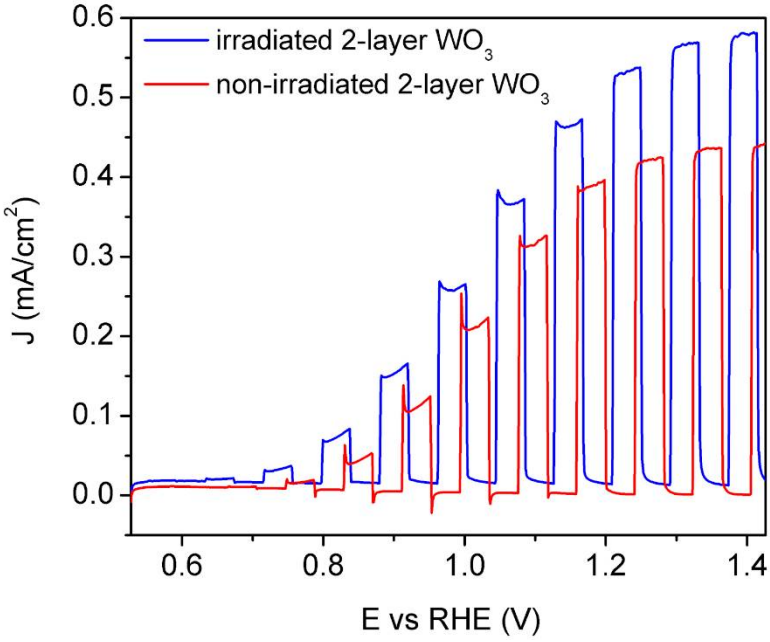

Figure S3. Chopped linear sweep voltammetry curves of double-layer WO_3 before and after modification with IPIB of 6 A/cm² ion beam current density.

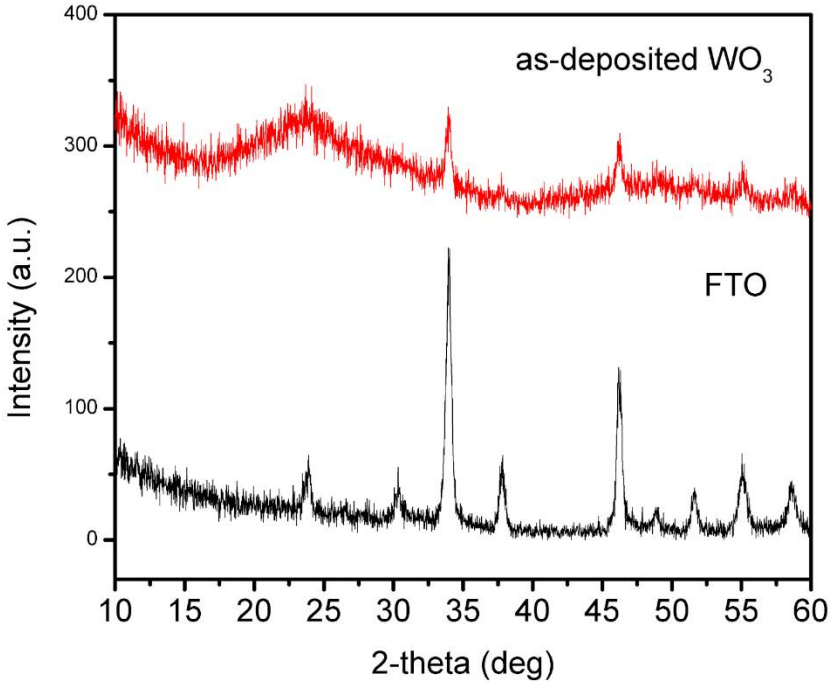

Figure S4. High resolution GI-XRD patterns of amorphous WO_3 and FTO substrate